

RESEARCH ARTICLE

Ultrasensitive solar-blind ultraviolet detection and optoelectronic neuromorphic computing using α -In₂Se₃ phototransistors

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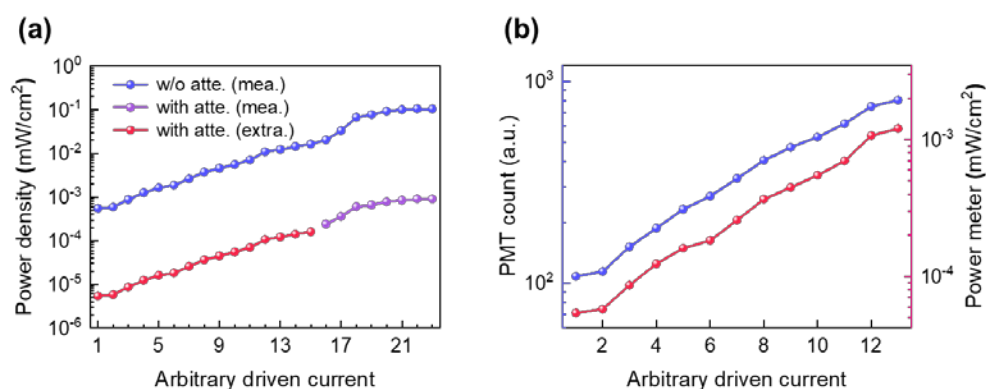
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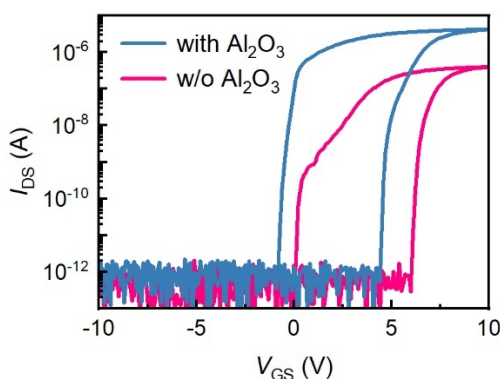
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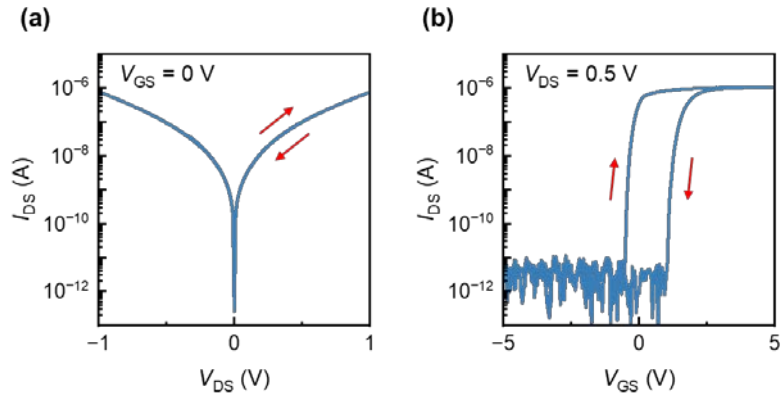
Supporting Information



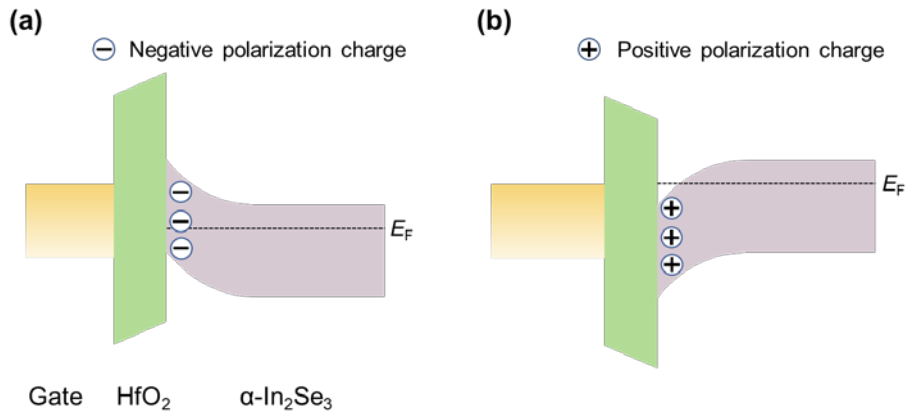
Supplementary Fig. S1 Calibration of the 275 nm light sources. (a) Measured (blue and purple) and extrapolated (red) power density using a power meter. The line in blue was measured without an attenuator. (b) Comparison between measured PMT count (blue) and extrapolated power density (red).



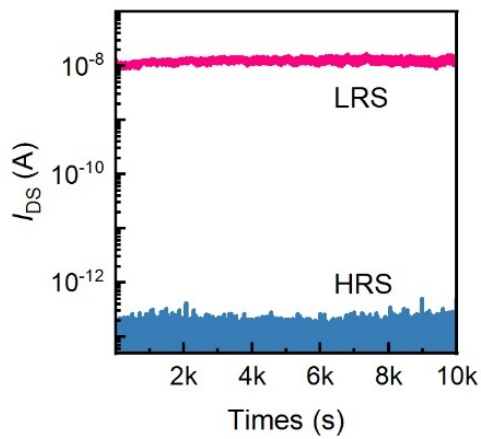
Supplementary Fig. S2 Transfer curves of the devices with and without the top Al₂O₃ layer. V_{DS}: 1 V.



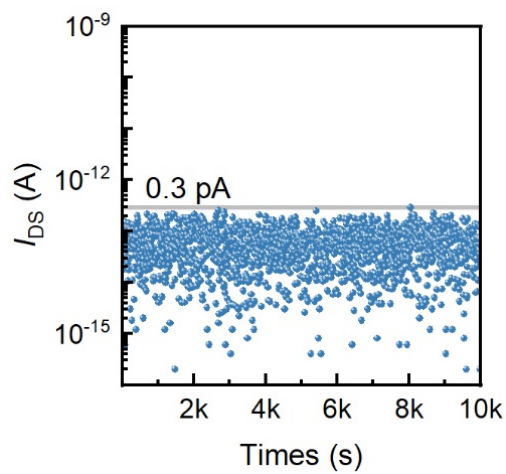
Supplementary Fig. S3 (a) Output and (b) transfer curves of the α -In₂Se₃ phototransistor.



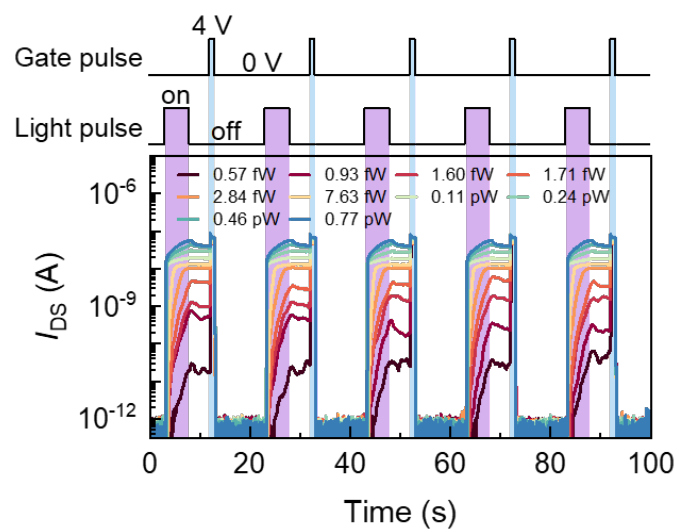
Supplementary Fig. S4 Band diagrams with the channel α -In₂Se₃ at different polarization states. (a) The band diagram after the device is set to the HRS due to a positive gate pulse applied ahead, in which negative polarization charges appear at the bottom surface of the channel α -In₂Se₃. (b) The band diagram after the device is stimulated to the LRS due to a negative gate pulse or a light pulse applied ahead, in which positive polarization charges appear at the bottom surface of the channel α -In₂Se₃ instead. Because a positive gate pulse can induce an upward electric field in channel α -In₂Se₃, an upward polarization is forced to appear and be strengthened so that negative polarization charges accumulate near the bottom surface of channel α -In₂Se₃ (a). For intrinsic α -In₂Se₃, the fermi level lies near the conduction band minimum, which endows it with n-type semiconducting nature. While in this HRS situation, the bounded negative polarization charges propel free electrons and induce an upward band bending near the surface, thus as a result, the fermi level shifts towards the valence band maximum near the surface, as shown in (a). On the contrary, a light pulse (or a negative gate pulse) induces the transition from upward polarization (HRS) to downward polarization (LRS) due to the downward imprint field, and then the resulting positive polarization charges near the bottom surface of the channel α -In₂Se₃ subsequently induces a downward band bending as shown in (b).



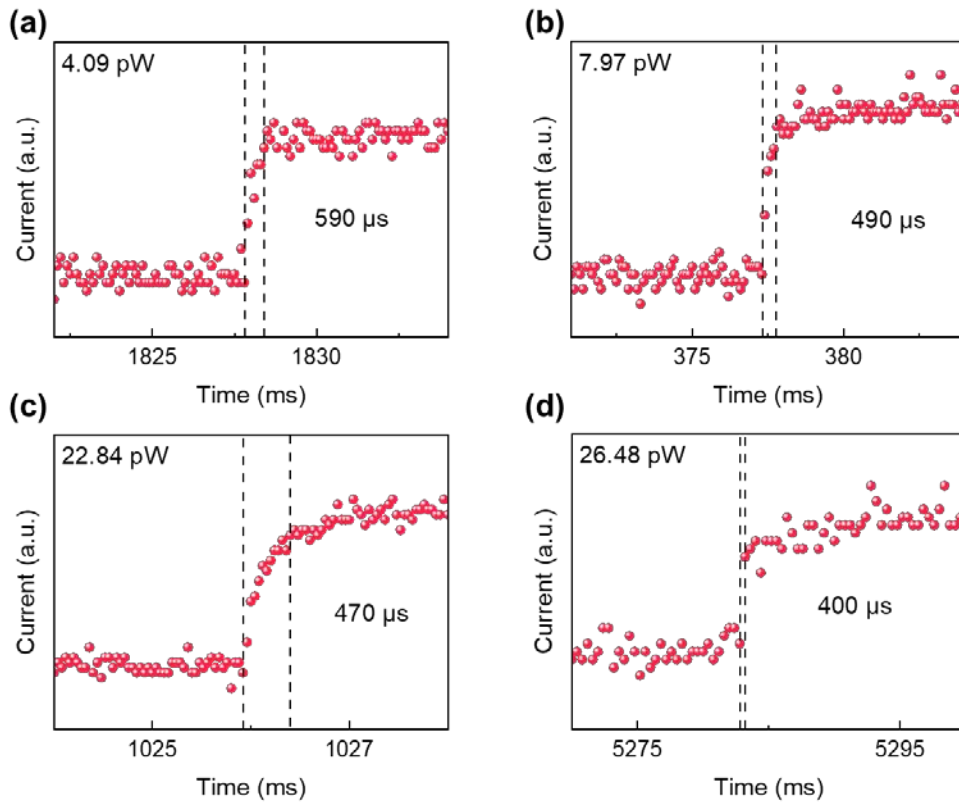
Supplementary Fig. S5 Long-term retention performance. The LRS was preset with a 360 nm light pulse of 4.4 fW and the HRS was preset with a gate pulse of 5 V.



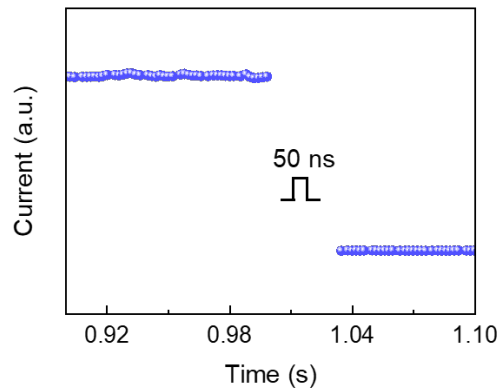
Supplementary Fig. S6 Retention of dark current (< 0.3 pA) for 10000 s. The device was preset to this low-current state with a positive gate pulse of 5 V amplitude. $V_{\text{read}} = 1$ V.



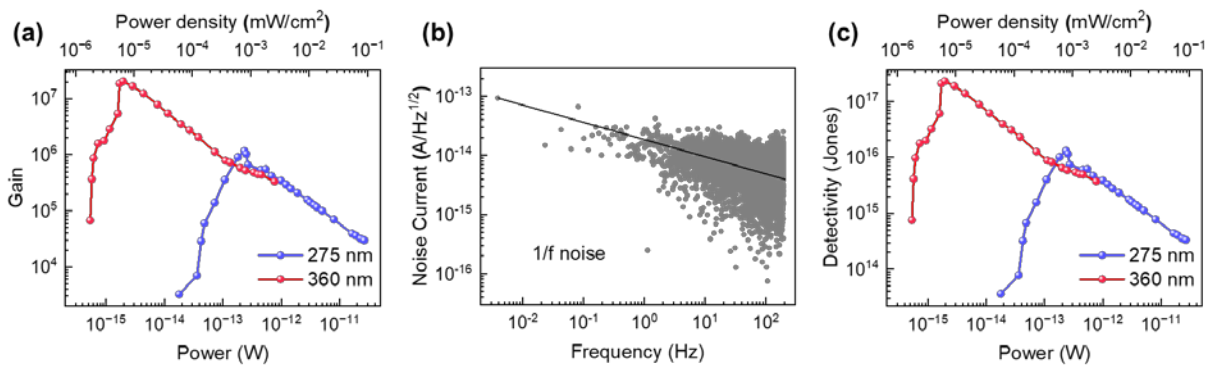
Supplementary Fig. S7 Temporal response to 360 nm light at various intensities. $V_{\text{DS}}: 1$ V.



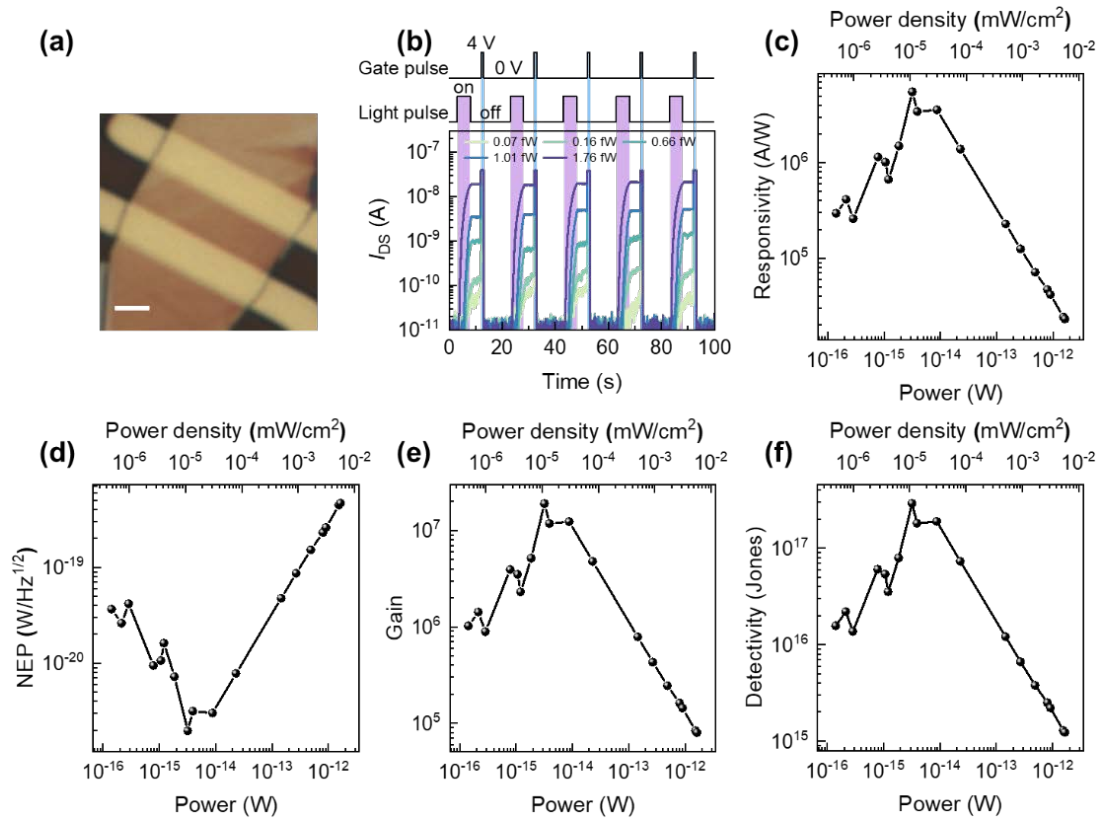
Supplementary Fig. S8 Response time of the device to 275 nm light at different intensities: (a) 590 μ s at 4.09 pW, (b) 490 μ s at 7.97 pW, (c) 470 μ s at 22.84 pW, (d) 400 μ s at 26.48 pW.



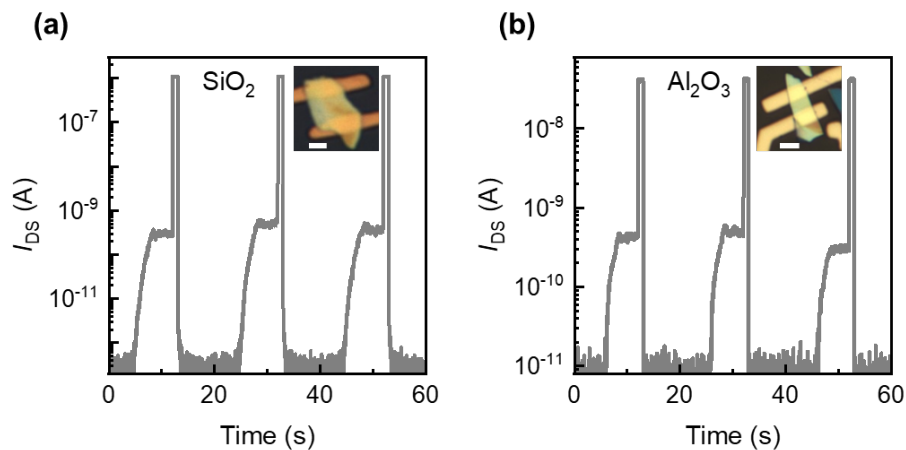
Supplementary Fig. S9 Response of the device to gate electrical pulse with a width of 50 ns.



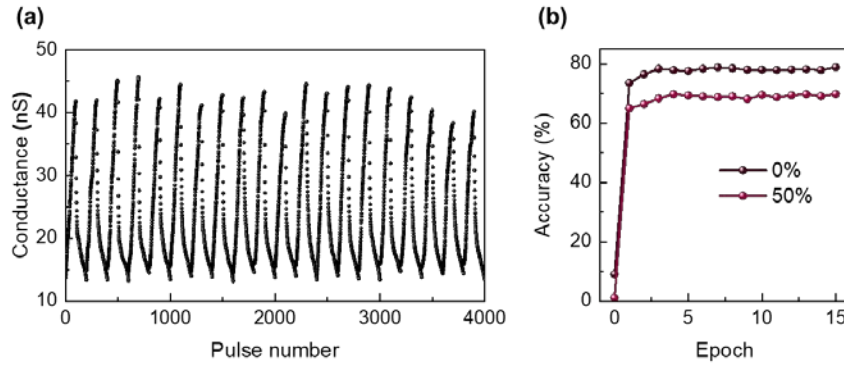
Supplementary Fig. S10 (a) Gain vs. power at 275 nm and 360 nm. (b) Noise current spectrum of the α -In₂Se₃ phototransistor. The dark line serves as a guide to the eye. (c) Detectivity vs. power at 275 nm and 360 nm.



Supplementary Fig. S11 Another device's geometrical and optoelectronic performance. (a) OM image. Scale bar: 2 μm. (b) Temporal response to 5 cycles of alternating optical-electrical pulses, with light intensities ranging from 0.07 fW to 1.76 fW. V_{DS} : 1 V. Figures of merit vs. power: (c) responsivity, (d) NEP, (e) gain and (f) detectivity. Wavelength: 360 nm.



Supplementary Fig. S12 Temporal response curves of devices with (a) 90 nm-thick SiO₂ and (b) 50 nm-thick Al₂O₃ as dielectric layers. The insets are the optical microscope images of corresponding devices with scale bars of 2 μm. The temporal response curves were tested using 3 cycles of alternating optical and electrical pulses with a period of 20 s. Optical pulse: width 5 s, amplitude 14.14 fW (a) and 9.30 fW (b). Gate electrical pulse: width 1 s, amplitude 5 V (a) and 2 V (b). V_{DS} : 1 V.



Supplementary Fig. S13 Demonstration of the α -In₂Se₃ phototransistor as a purely electrical synapse in an ANN. (a) Purely electrical pulse-dependent LTP and LTD behaviors of the synapse. During each conductance (weight) increasing/decreasing period, 100 negative/positive gate pulses with a width of 1 ms and an amplitude of -4/0.3 V were periodically applied with a period of 50 ms. (b) Recognition accuracy over F-MNIST dataset as a function of training epoch with different dataset noise levels: 0% and 50%.

Supplementary Table 1 Comparison of figures of merit among various materials/structures.

Material/structure	Power (W)	Responsivity (A/W)	Detectivity (Jones)	NEP (W/Hz ^{1/2})	Gain	Wavelength (nm)	Ref.
α -In ₂ Se ₃	5.37×10^{-16}	4.5×10^6	2.3×10^{17}	2.4×10^{-21}	1.6×10^7	360	This work
α -In ₂ Se ₃	1.79×10^{-14}	2.6×10^5	1.3×10^{16}	4.2×10^{-20}	1.2×10^6	275	This work
h-BN	3.25×10^{-12}	2.75	3.2×10^{13}	4.69×10^{-17}	21	160	[1]
NiPS ₃	1.99×10^{-8}	0.126	1.22×10^{12}	2.32×10^{-16}	0.6	254	[2]
Graphene/ β -Ga ₂ O ₃	4×10^{-5}	39.3	5.92×10^{13}	1.51×10^{-14}	192	254	[3]
Te	8×10^{-11}	6.5×10^4	/	/	3.1×10^5	261	[4]
GaSe/WS ₂	5×10^{-10}	3	/	/	11	350	[5]
BP/MoS ₂	2.5×10^{-11}	207.3	/	/	920	280	[6]
BP	2.65×10^{-10}	9×10^4	3×10^{13}	1.21×10^{-17}	3.6×10^5	310	[7]
Graphene/h-BN/ZnO	1.25×10^{-6}	1.35×10^4	/	/	4.6×10^3	365	[8]
Bi ₂ Te ₃	5.02×10^{-3}	6.3×10^{-3}	/	/	0.02	365	[9]
SnS ₂ /ZnO _{1-x} S _x	5.6×10^{-5}	8.28×10^{-3}	5.1×10^{10}	1.39×10^{-12}	0.03	365	[10]
MnPS ₃	4.87×10^{-12}	288	6.48×10^{11}	8.79×10^{-16}	981	365	[11]
PbI ₂	2×10^{-8}	0.51	4×10^{10}	1.12×10^{-13}	1.7	375	[12]
GaN	2.25×10^{-7}	2.5	/	4.5×10^{-13}	8.6	360	[13]
Diamond	2.4×10^{-4}	21.8	/	/	124	218	[14]
AlGa _N	1×10^{-6}	200	/	/	765	325	[15]
Graphene QDs	4.2×10^{-6}	2.1×10^{-3}	9.59×10^{11}	3.3×10^{-13}	0.01	254	[16]
MoS ₂ /Cs ₃ Bi ₂ I ₉	3.9×10^{-13}	1.42	1.15×10^{13}	1.45×10^{-16}	5.4	325	[17]
PEDOT:PSS/ZnO	1.38×10^{-4}	0.0035	7.5×10^9	3.27×10^{-11}	0.01	325	[18]
ZnO QDs/graphene	2.3×10^{-12}	9.9×10^8	1×10^{14}	1.3×10^{-18}	3.6×10^9	340	[19]
ZnO/Zn ₂ SnO ₄	1.68×10^{-9}	3.5×10^6	9×10^{17}	5.56×10^{-20}	1.4×10^7	305	[20]

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